

DELPHION

No active trail

Select OK

Stop track

RESEARCH

PRODUCTS

INSIDE DELPHION

Log Out Work Files Saved Searches

My Account

Search: Quick/Number Boolean Advanced Derwent

The Delphion Integrated View

Buy Now: PDF | [More choices...](#)

Tools: Add to Work File: Create new Work File

View: [Expand Details](#) | [INPADOC](#) | Jump to: [Top](#)Go to: [Derwent](#)☒ [Email this to a](#)

Title: **WO0009258A1: METHOD AND APPARATUS FOR TREATING WASTE GAS CONTAINING FLUOROCH**[\[French\]](#)

Derwent Title: Decomposition of fluorine-containing compound in exhaust gas used in etching semiconductor devices by contacting exhaust gas containing fluorine-containing compound with aluminum oxide [\[Derwent Record\]](#)

Country: **WO** World Intellectual Property Organization (WIPO)

Kind: **A1** Publ. of the Int. Appl. with Int. search report ¹

Inventor: **MORI, Yoichi**; 1-6-18-B202, Jukkenzaka, Chigasaki-shi, Kanagawa 253-0045, Japan

Assignee: **EBARA CORPORATION**, 11-1, Haneda Asahi-cho, Ohta-ku, Tokyo 144-8510, Japan
[News, Profiles, Stocks and More about this company](#)

Published / Filed: **2000-02-24 / 1999-08-05**

Application **WO1999JP0004224**

Number:

IPC Code: **B01J 21/06**; **B01D 53/86**;

ECLA Code: **B01D53/86L**; **B01J21/04**;

Priority Number: **1999-03-04 JP1999000056754**

Abstract: A method and apparatus for decomposing a fluorochemical, e.g., C₂F₆, by bringing a waste gas (1) containing the fluorochemical into contact with an aluminum oxide (3), e.g., .ggr.-alumina, heated at, e.g., 800 to 900 °C. H₂ may be present therein in an amount sufficient for converting the fluorine atoms of the fluorochemical to HF. The fluorochemical can be decomposed to a high degree. The aluminum oxide has a long life, and CO generation is little. [\[French\]](#) [\[Japanese\]](#)

Attorney, Agent or Firm: **SHAMOTO, Ichio** ;

INPADOC [Show legal status actions](#)

Buy Now: [Family Legal Status Report](#)

Legal Status:

Designated **JP KR US, European patent: DE FR GB**

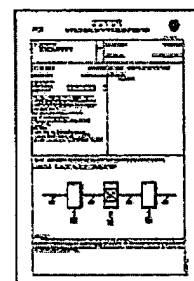
Country:

Family: [Show 4 known family members](#)



Forward [Go to Result Set: Forward references \(2\)](#)

References:

Buy PDF	Patent	Pub.Date	Inventor	Assignee	Title

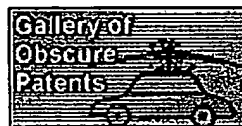
High
ResolLow
Resol

34 p

	US6790421	2004-09-14	Mori; Yoichi	Ebara Corporation	Method for treating exhaust gas containing fluorine-containing compou
	US6764666	2004-07-20	Mori; Yoichi	Ebara Corporation	Process for treating gas containing fluorine-containing compounds and C

Other Abstract
Info:

CHEMABS 132(12)155908V CHEMABS 132(12)155908V [DERABS C2000-205923](#) [DERABS C2000-205923](#)



[Nominate this for the Gallery...](#)

THOMSON

Copyright © 1997-2005 The Thomson Corp

[Subscriptions](#) | [Web Seminars](#) | [Privacy](#) | [Terms & Conditions](#) | [Site Map](#) | [Contact Us](#) | [Help](#)



PCT

特許協力条約に基づいて公開された国際出願

<p>(51) 国際特許分類6 B01J 21/06, B01D 53/86</p>	<p>A1</p>	<p>(11) 国際公開番号 WO00/09258</p> <p>(43) 国際公開日 2000年2月24日 (24.02.00)</p>
<p>(21) 国際出願番号 PCT/JP99/04224</p> <p>(22) 国際出願日 1999年8月5日 (05.08.99)</p> <p>(30) 優先権データ 特願平10/244356 1998年8月17日 (17.08.98) JP 特願平11/56754 1999年3月4日 (04.03.99) JP</p> <p>(71) 出願人 (米国を除くすべての指定国について) 株式会社 荏原製作所 (EBARA CORPORATION) [JP/JP] 〒144-8510 東京都大田区羽田旭町11番1号 Tokyo, (JP)</p> <p>(72) 発明者; および (75) 発明者/出願人 (米国についてのみ) 森 洋一 (MORI, Yoichi) [JP/JP] 〒253-0045 神奈川県茅ヶ崎市十間坂1-6-18-B202 Kanagawa, (JP)</p> <p>(74) 代理人 弁理士 社本一夫, 外 (SHAMOTO, Ichio et al.) 〒100-0004 東京都千代田区大手町二丁目2番1号 新大手町ビル206区 ユアサハラ法律特許事務所 Tokyo, (JP)</p>		<p>(81) 指定国 JP, KR, US, 欧州特許 (DE, FR, GB)</p> <p>添付公開書類 国際調査報告書</p>
<p>(54) Title: METHOD AND APPARATUS FOR TREATING WASTE GAS CONTAINING FLUORO-CHEMICAL</p> <p>(54) 発明の名称 フッ素含有化合物を含む排ガスの処理方法及び装置</p> <div data-bbox="224 1276 1317 1587"> </div> <p>(57) Abstract A method and apparatus for decomposing a fluorochemical, e.g., C₂F₆, by bringing a waste gas (1) containing the fluorochemical into contact with an aluminum oxide (3), e.g., γ-alumina, heated at, e.g., 800 to 900 °C. H₂ may be present therein in an amount sufficient for converting the fluorine atoms of the fluorochemical to HF. The fluorochemical can be decomposed to a high degree. The aluminum oxide has a long life, and CO generation is little.</p>		